

IN THE CLAIMS:

Please substitute the following claims for the same-numbered claims in the application:

1. (Currently Amended) An apparatus comprising:
a holder adapted to hold and rotate a substrate;
a shield surrounding said substrate; and
a dispenser positioned to dispense a fluid on said substrate such that, when said substrate is rotated and said fluid is dispensed, said fluid and foreign matter particles are ejected from said substrate towards said shield,
wherein a surface of said shield facing said substrate comprises a semi-permeable material adapted to prevent said fluid and said foreign matter particles from forming into a mist and being re-deposited back on said substrate.
2. (Currently Amended) The apparatus of claim 1, wherein said semi-permeable material has one of perforations and screen holes facing said substrate ~~prevents fluid ejected from the surface of the rotating substrate from forming into a mist and being re-deposited back on said substrate.~~
3. (Canceled).
4. (Currently Amended) The apparatus in claim 1, wherein said semi-permeable material comprises one of ~~an absorptive material,~~ a screen material, and a perforated material ~~and a finned~~

material.

5. (Original) The apparatus in claim 1, wherein said semi-permeable material comprises a disposable material and is adapted to be periodically removed from said shield and replaced.

6. (Original) The apparatus in claim 1, wherein said semi-permeable material comprises a permanent part of said shield.

7. (Original) The apparatus in claim 1, wherein fluid ejected from the surface of the rotating substrate is collected by and drains down said semi-permeable material.

8. (Currently Amended) A cleaning apparatus used during the production of semiconductor wafers, said apparatus comprising:

a holder adapted to hold and rotate a semiconductor wafer;

a shield surrounding said semiconductor wafer; and

a dispenser positioned to dispense a cleaning fluid on said semiconductor wafer such that, when said semiconductor wafer is rotated and said cleaning fluid is dispensed, said cleaning fluid and foreign matter particles are ejected from said semiconductor wafer towards said shield,

wherein a surface of said shield facing said semiconductor wafer comprises a semi-permeable material having absorptive fins and

wherein said semi-permeable material with said absorptive fins prevents said cleaning fluid and said foreign matter particles from forming into a mist and being re-deposited back on said semiconductor wafer.

9. (Canceled).

10. (Currently Amended) The apparatus in claim [[9]] 8, wherein said absorptive fins are adapted to provide air flow and fluid flow control ~~mist comprises said cleaning fluid and foreign material particles.~~

11. (Currently Amended) The apparatus in claim 8, wherein said semi-permeable material comprises one of an absorptive material, a screen material, and a perforated material ~~and a finned material.~~

12. (Original) The apparatus in claim 8, wherein said semi-permeable material comprises a disposable material and is adapted to be periodically removed from said shield and replaced.

13. (Original) The apparatus in claim 8, wherein said semi-permeable material comprises a permanent part of said shield.

14. (Original) The apparatus in claim 8, wherein cleaning fluid ejected from the surface of the rotating semiconductor wafer is collected by and drains down said semi-permeable material.

15-20. (Canceled).

21. (New) An apparatus comprising:
a holder adapted to hold and rotate a substrate;

a shield surrounding said substrate;

a dispenser positioned to dispense a fluid on said substrate such that, when said substrate is rotated and said fluid is dispensed, said fluid and foreign matter particles are ejected from said substrate towards said shield; and

a disposable liner on a surface of said shield facing said substrate,

wherein said disposable liner comprises a semi-permeable membrane having vertically oriented fins and one of perforations and screen openings facing said substrate, and

wherein said semi-permeable membrane with said vertically oriented fins and said one of said perforations and said screen openings prevents said fluid and said foreign matter particles from forming into a mist and being re-deposited back on said substrate.

22. (New) The apparatus in claim 21, wherein said vertically oriented fins are adapted to provide air flow and fluid flow control.

23. (New) The apparatus in claim 21, wherein said semi-permeable membrane comprises one of a screen material and a perforated material.

24. (New) The apparatus in claim 21, wherein said vertically oriented fins comprise absorptive vertically oriented fins.

25. (New) The apparatus in claim 21, wherein said disposable liner is adapted to be periodically removed from said shield and replaced.

26. (New) The apparatus in claim 21, wherein said disposable liner is adapted to collect and drain said fluid and said foreign matter particles ejected from said substrate.